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Title: ASTERIX & LANL Experiences

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ASTERIX/LANL EXPERIENCES

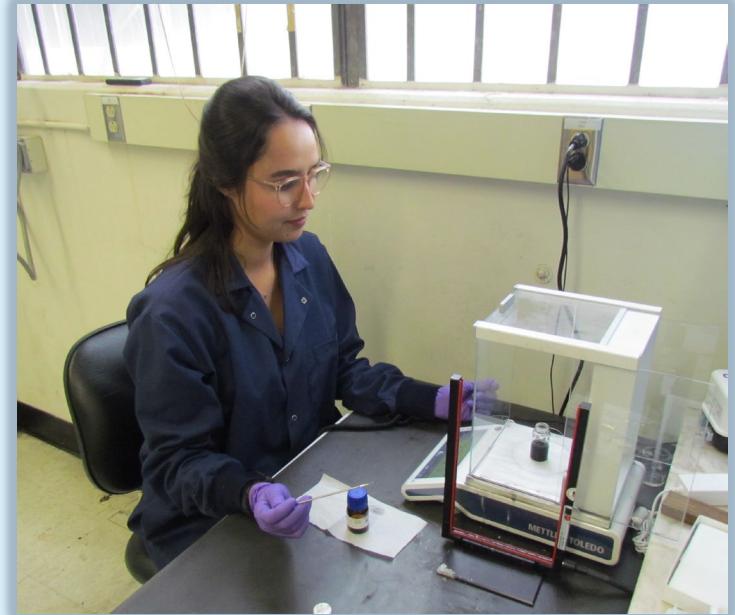


ASTERIX TIMELINE



GRADUATE RESEARCH ASSISTANT

- Fuel Cells
 - Fabrication and characterization of Pt inks
 - Fabrication and characterization of MEAs
- Thin Films
 - Fabrication of thin films using PVD
 - Characterization of thin films
 - Assembly of new PVD system
- Mentoring
 - Collaborating and assisting FIU senior design teams
 - Assisting new summer students



THIN FILMS RESEARCH

RESEARCH ARTICLE | MARCH 24 2023

Effects of processing parameters on the morphologies of complex sesquioxide thin films

Sofia K. Pinzon  ; James A. Valdez  ; Vancho Kocevski  ; J. K. Baldwin  ; Blas P. Uberuaga  ; Cortney R. Kreller  ; Benjamin K. Derby  



Journal of Vacuum Science & Technology A 41, 033404 (2023)

<https://doi.org/10.1116/6.0002398>

JVSTA

Journal of Vacuum Science & Technology A | 2nd Series | Volume 41, Number 3 | May/June 2023

Atomic Layer Etching

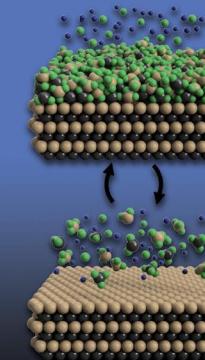


Image Credit: J. A. Michaels, N. Delega, Y. Tsal'yanyan, J. R. Perino, D. D. Arochakom, J. G. Eder, and F. J. Heijmans, JVST A-41 (3), 101108/000247 (2023).

Review Articles:
Influence of local chemical environment and external perturbations of porphyrins on surfaces
José J. Ortí-García and Rebeca C. Quinteros

Perspective

Perspective on improving the quality of surfaces and material data from the literature with a focus on x-ray photoelectron spectroscopy (XPS)
George H. Major, Joshua W. Pinder, Daniel E. Austin, Donald R. Baker, Steven L. Castle, Jan Cechal, B. Maxwell Clark, Hagai Cohen,
Jonathan Counsell, Alberto Herrera-Gómez, Pavitra Govindan, Seong H. Kim, David J. Morgan, Robert L. Ogall, Cedric J. Powell, Stanislaw Prusa,
Adam Roberts, Mario Rocca, Nando Shirahata, Tomás Skoda, Emily F. Smith, Regina C. So, John E. Stavila, Jennifer Strunk, Andrew Teplyakov,
Jeff Terry, Stephen G. Weber, and Matthew R. Linford

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ASTERIX/LANL EXPERIENCE

- Specialized hands-on learning and experience
- Exposure to different projects
- Collaboration with other scientists/engineers/students
- Expand network
- Access to many resources

